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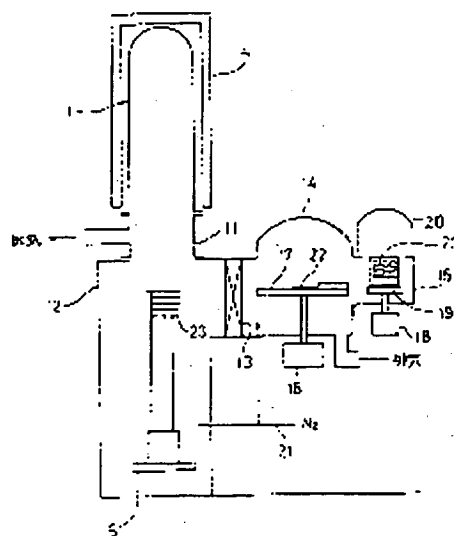
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(54) CVD DEVICE

(57)Abstract:

PURPOSE: To prevent the oxidation after CVD and contamination with dust by providing a gate valve between a load-locking chamber and a load-locking spare chamber and conveying a wafer from a cassette into a reaction chamber in an airtight vessel.

CONSTITUTION: A gate valve 13 provided between the load-locking chamber 12 and the load-locking spare chamber 14 is closed, and the vertical reaction chamber 1 and the load-locking chamber 12 connected to the lower part of the chamber 1 are airtightly closed. A cassette changed with a wafer 23 is placed on the cassette receiver 19 of a cassette elevator 18. The spare chamber 14 and a cassette chamber 15 are then evacuated. The valve 13 is opened, and the wafer 23 is transferred to an elevator mechanism 5 by a wafer transfer machine 16. The valve 13 is then closed, the reaction chamber 1 and the load-locking chamber 12 are supplied with a gaseous reactant, and CVD is applied.



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